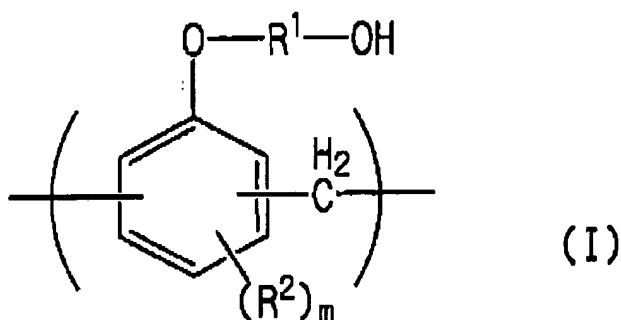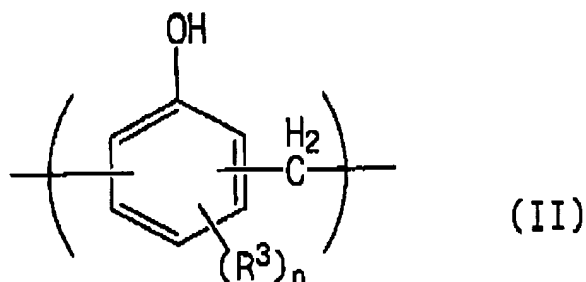Appl. No.   :   10/564,453
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AMENDMENTS TO THE CLAIMS

1.   (Original) A positive photoresist composition comprising an alkali-soluble

novolak resin (A) containing a structural unit (a1) represented by a general formula (I) shown
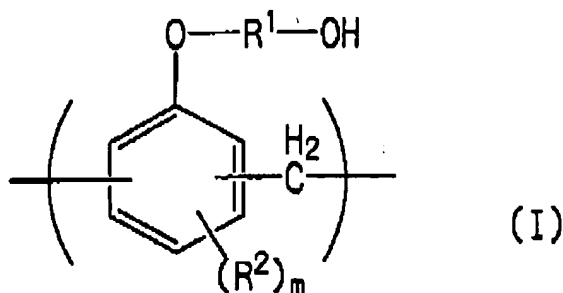
below:

(I)

[wherein, R^1 represents an alkylene group of 1 to 5 carbon atoms, R^2 represents a hydrogen atom,

a hydroxyl group, or an alkyl group of 1 to 4 carbon atoms, and m represents an integer of 1 to 3],

and a structural unit (a2) represented by a general formula (II) shown below:

(II)

[wherein, R^3 represents a hydrogen atom, a hydroxyl group, or an alkyl group of 1 to 4 carbon

atoms, and n represents an integer of 1 to 3], and a photosensitizer (B).

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2.   **(Original)** A positive photoresist composition comprising an alkali-soluble

novolak resin (A') containing a structural unit (a1) represented by a general formula (I) shown

below:

(I)

[wherein, R^1 represents an alkylene group of 1 to 5 carbon atoms, R^2 represents a hydrogen atom,

a hydroxyl group, or an alkyl group of 1 to 4 carbon atoms, and m represents an integer of 1 to 3],

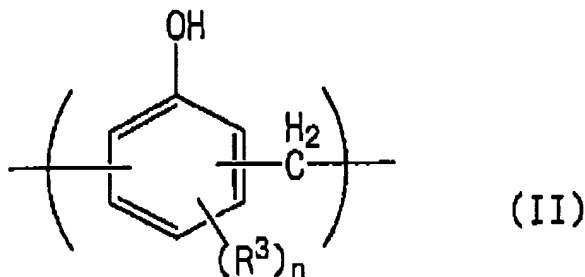and a structural unit (a2) represented by a general formula (II) shown below:

(II)

[wherein, R^3 represents a hydrogen atom, a hydroxyl group, or an alkyl group of 1 to 4 carbon

atoms, and n represents an integer of 1 to 3], wherein a portion of hydrogen atoms of said

hydroxyl groups contained within said resin are substituted with 1,2-

naphthoquinonediazidesulfonyl groups.

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3.   **(Original)** A positive photoresist composition according to claim 2, further comprising a photosensitizer (B).

4.   **(Currently Amended)** A method of forming a resist pattern comprising the steps of applying a positive photoresist composition according to <u>any one of claim 1 through</u> claim 3 to a substrate, conducting a prebake, performing selective exposure, and then performing alkali developing to form the resist pattern.

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